

U.S. Department of Commerce, Patent and Trademark Office

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Serial No.

M-11912 US

10/033,114

INFORMATION DISCLOSURE STATEMENT BY APPLICANT

(Use several sheets if necessary)

Applicants

Tai-Peng Lee et al.

Filing Date

Group

October 22, 2001

Not assigned yet

U.S. Patent Documents

*Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
	AA					
	AB					
	AC					
	AD					
	AE					
	AF					
	AG					
	AH					
	AI					
	AJ					
	AK					

Foreign Patent Documents

	Document	Date	Country	Class	Subclass	Translation	
						Yes	No
	AL						
	AM						
	AN						
	AO						
	AP						

OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

JAG	AQ	S.V. Nguyen, "High Density Plasma Chemical Vapor Deposition of Silicon-based Dielectric Films For Integrated Circuits" (visited 26 July 2001) < http://www.research.ibm.com/journal/rd/431/nguyen.html >.
	AR	
	AS	

Examiner

Date Considered

June 7, 2003

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with your communication to applicant.